

20th Anniversary of KSDT  
**KISM 2022**  
Korean International Semiconductor Conference on Manufacturing Technology 2022  
November 13-16, 2022 | Paradise Hotel Busan (Haeundae Beach), Busan, Korea

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| <b>Session Title:</b> | <b>[MD1] EUV Imaging</b>                      |
| <b>Session Date:</b>  | <b>November 14 (Mon.), 2022</b>               |
| <b>Session Time:</b>  | <b>13:00-14:40</b>                            |
| <b>Session Room:</b>  | <b>Room D (Sidney Room, 2F)</b>               |
| <b>Session Chair:</b> | <b>Prof. Jinho Ahn (Hanyang Univ., Korea)</b> |

**[MD1-1] [Invited]** 13:00-13:30

**Challenges and Chances on EUV Lithography**

**Chan Hwang and Seongbo Shim (Samsung Electronics Co., Ltd., Korea)**

**[MD1-2] [Invited]** 13:30-14:00

**Extension of EUV Lithography Technology for Next Patterning Solutions**

**Jung Sik Kim, Jinhyung Kim, Bumki Shin, Junggun Heo, and Sarohan Park (SK hynix, Korea)**

**[MD1-3]** 14:00-14:20

**Overlay and CD Uniformity Variation due to Wafer Thermal Deformation Caused by EUV Exposure**

**Hee-Chang Ko, Won-Young Choi, and Hye-Keun Oh (Hanyang Univ., Korea)**

**[MD1-4]** 14:20-14:40

**Effect of Pellicle Wrinkles on EUV Reflectivity and Local Critical Dimension**

**Seung Chan Moon, Dong Gi Lee, Jin Hyuk Choi, and Jinho Ahn (Hanyang Univ., Korea)**